

Polymer–Ceramic Powder Composite  
Embedded Capacitor Materials for  
Organic Substrates Applications

백 경 욱 교수  
(KAIST)



# *Epoxy/BaTiO<sub>3</sub> (SrTiO<sub>3</sub>) Composite Films for High Dielectric Constant and Low Tolerance Embedded Capacitors in Organic Substrates*

*Kyung-Wook Paik*

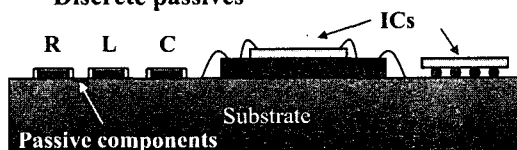
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Korea Advanced Institute of Science & Technology*

SMT/PCB 기술 세미나  
2/15/2006

## *Embedded Passives*

### ■ Embedded Passives

- Discrete passives



- Embedded passives



### ■ Advantages of Embedded Passives

- Smaller area
- Shorter interconnection length
- Less solder joints

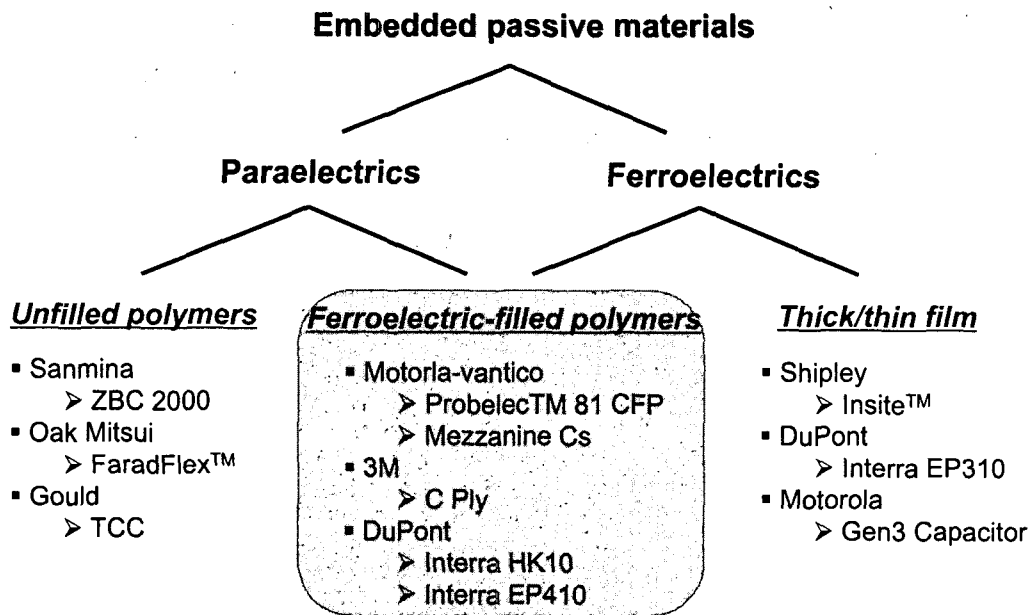


- Miniaturization
- Higher electrical performance
- Better reliability

### ■ Embedded capacitors

- 40% of total passive components
- Important roles in electronic circuits – decoupling, bypass, etc.
- Thin film or thick film materials

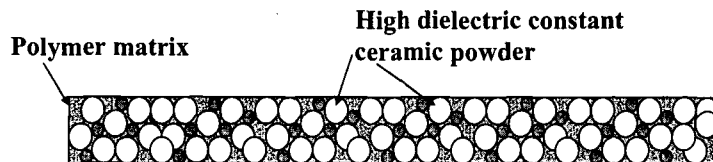
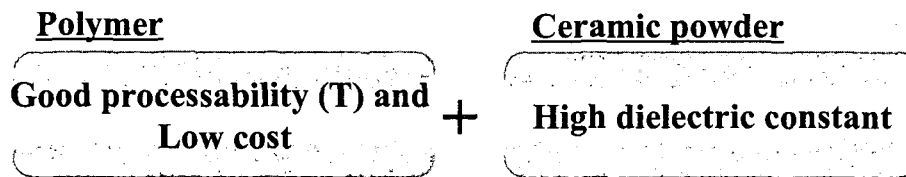
## Overview of Commercial Capacitor Technology



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## Why polymer/ceramic composite materials?



- Polymer: Epoxy (compatible with PCB), Polyimide, PVDF
- Ceramic powder: BaTiO<sub>3</sub>, SrTiO<sub>3</sub>, Pb(Mg,Nb)O<sub>3</sub>-PbTiO<sub>3</sub>, BST

### ■ Epoxy/BaTiO<sub>3</sub> & SrTiO<sub>3</sub> composites

- BaTiO<sub>3</sub> & SrTiO<sub>3</sub>: well-known and commercially available high dielectric constant and low-Q ceramic powders
- Epoxy: compatible with PCB

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## ***Demands of new embedded capacitor materials***

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### **■ Requirements for embedded capacitor materials**

- High dielectric constant
- Low tolerance ( $< \pm 5\%$ ) of capacitance
- Processability
- Low cost

$$\frac{C}{A} = \epsilon_0 \epsilon_r \frac{1}{d}$$

### **■ Desirable characteristics of embedded capacitor materials**

- No materials waste
- Uniform thickness  $\rightarrow$  low tolerance of capacitance
- B-stage film  $\rightarrow$  long shelf life
- Transferable films or pastes  $\rightarrow$  capacitors fabrication on selected areas

***Advanced embedded capacitor materials is needed!!***

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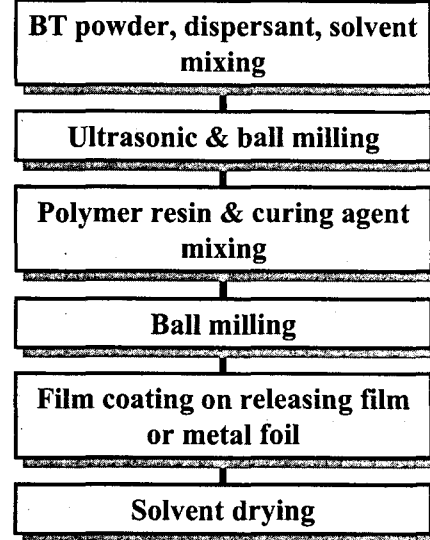
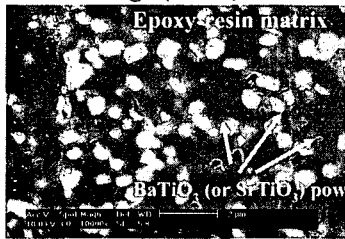
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## **Epoxy/BaTiO<sub>3</sub> (& SrTiO<sub>3</sub>) Composite Embedded Capacitor Films (ECFs)**

# Material Formulation for ECFs

Materials:  $BaTiO_3$ ,  $SrTiO_3$  powder, epoxy resin, curing agent, dispersant, solvent

- ❖ Ceramic powder
  - $BaTiO_3$  : high dielectric constant
  - $SrTiO_3$  : low loss & stable frequency dependence
- ❖ Specially formulated epoxy resin
  - Epoxy
  - Good compatibility with PCB & processability in B-stage (not cured at film stage)
- ❖ X-section image (ECFs)



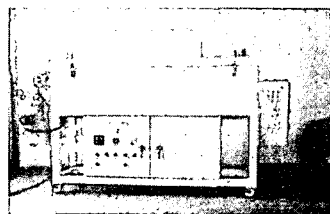
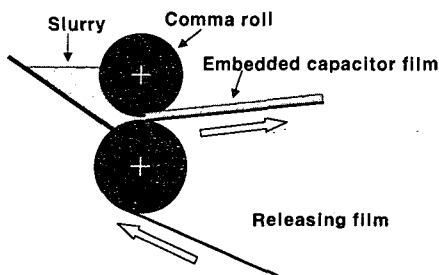
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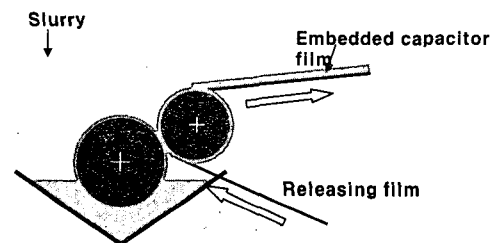
## ECF Film Formation Methods

### ❖ Two film coating methods

- Comma roll (Film thickness >10um)



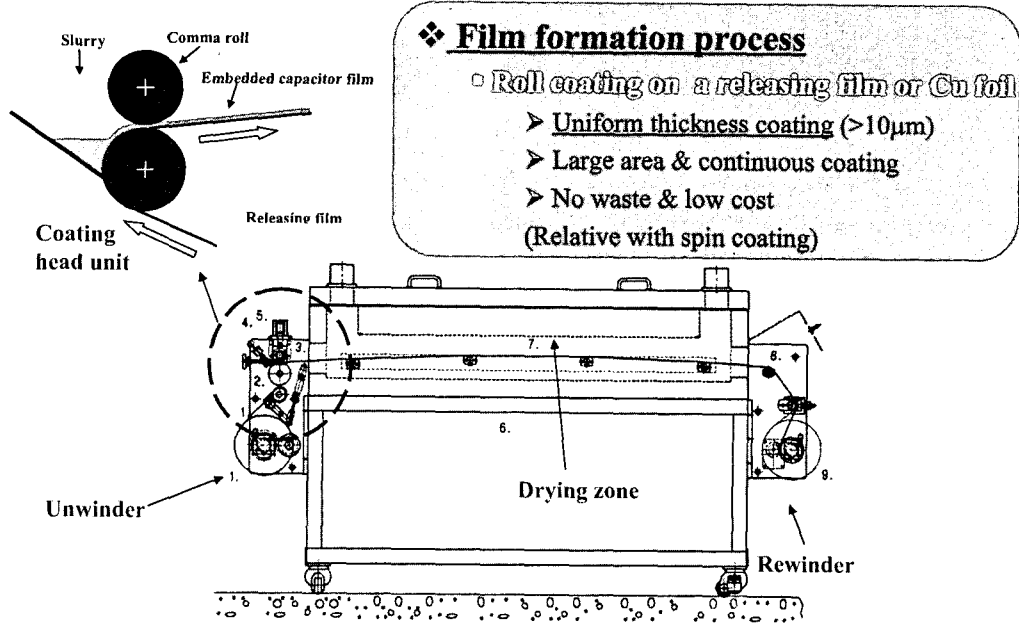
- Gravure roll (Film thickness < 10um)



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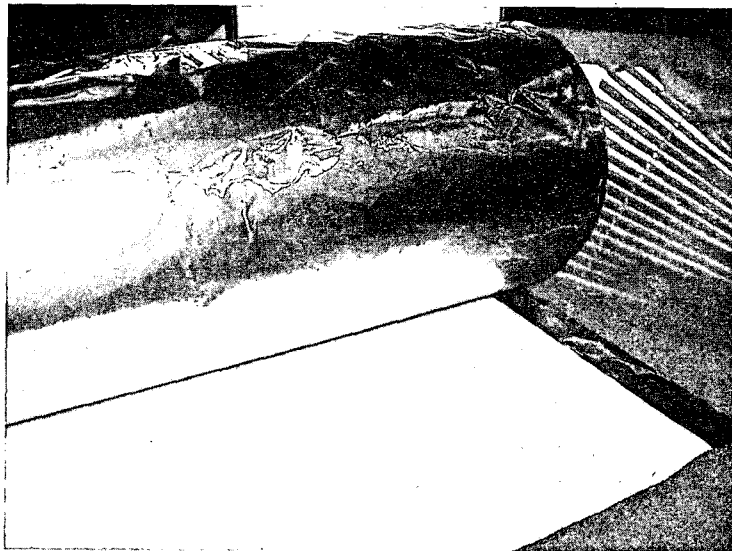
## Coating Processes Using a Roll Coating Method



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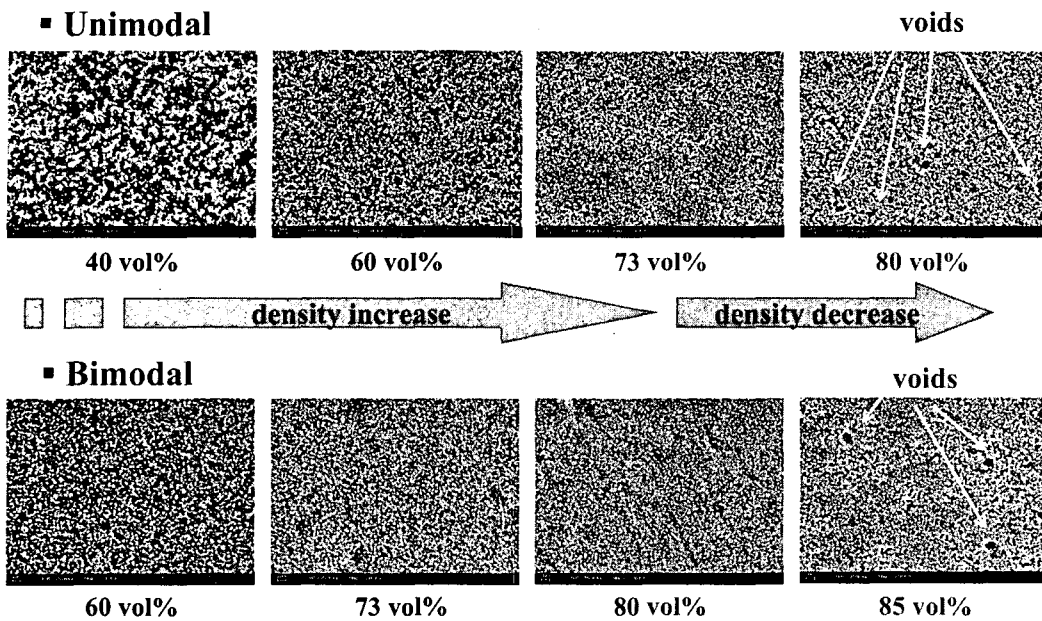
## ECFs coated on a copper foil



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## ECF surface morphology (Comma roll coated)



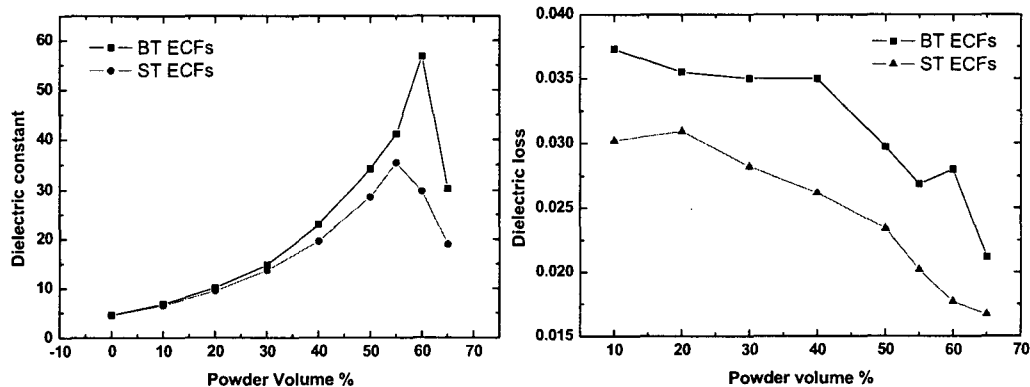
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## Dielectric Constant & Dielectric Loss

◆ Measurement condition

- Level 1V, frequency 100kHz
- Equipment: HP4284A LCR meter



- Dielectric constant increased with powder content.
- Epoxy/SrTiO<sub>3</sub> composite shows lower dielectric constant and lower loss than epoxy/BaTiO<sub>3</sub>.

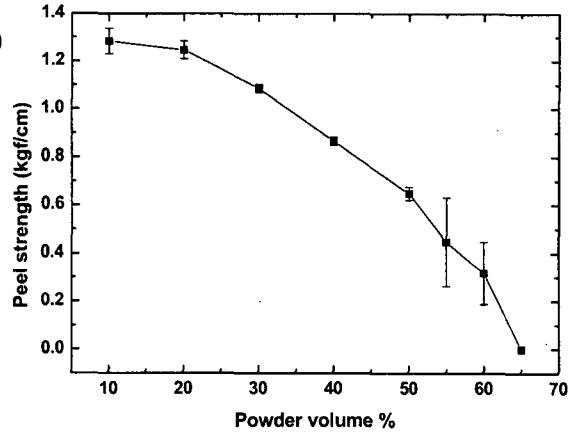
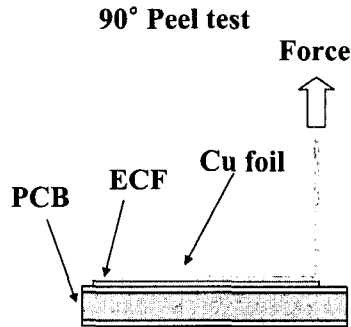
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# ECF Adhesion Strength on Cu Foils

- ◆ Measurement condition
  - Peel speed : 10mm/cm
  - Equipment: tensile tester (Ck trade ®)

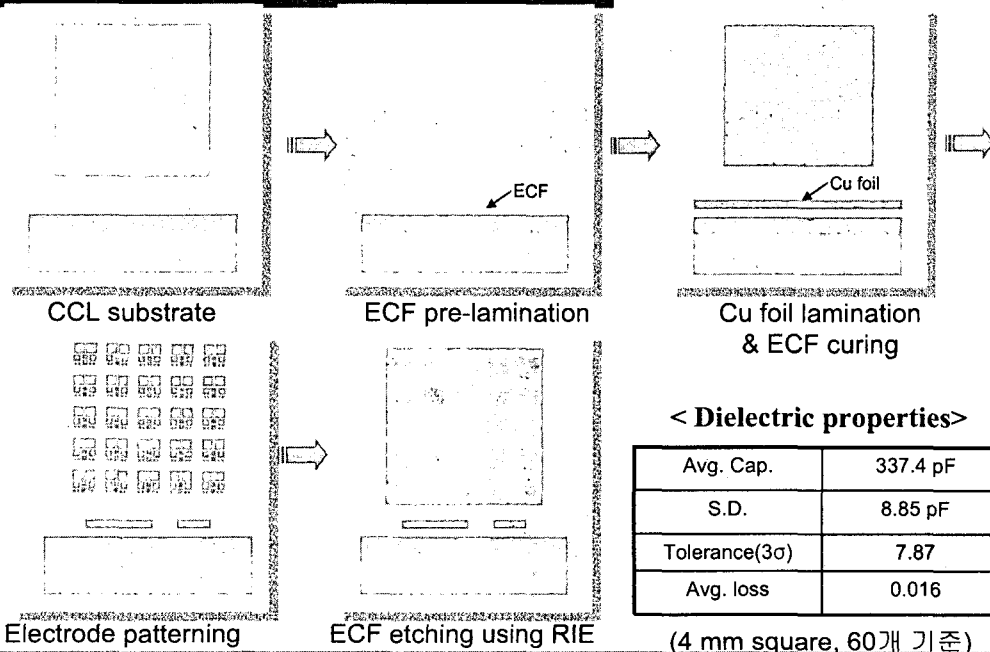


- Interface adhesion strength between ECF and Cu foil
- Smooth surface of Cu foil was used.
- Thickness: Cu foil-18 $\mu$ m, ECF- 10~20 $\mu$ m

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## Capacitors fabrication processes of ECFs coated on a PET film

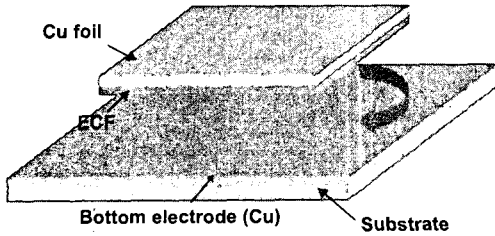


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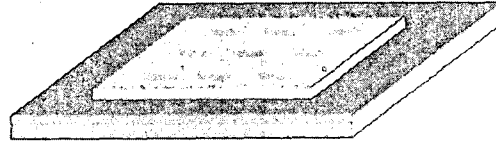
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*Capacitors fabrication processes of ECFs coated on a copper foil*

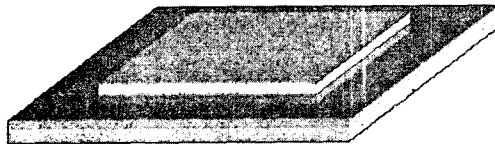
**1. Pre lamination using roll (50°C)**



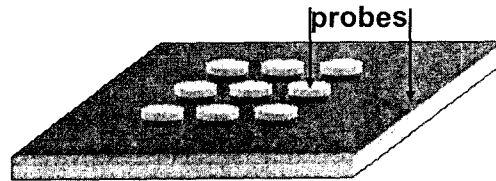
**3. Electrodes patterning (Cu thickness: 12µm)**



**2. Lamination using air laminator (180°C, 3.5kgf/cm<sup>2</sup>, 10min)**



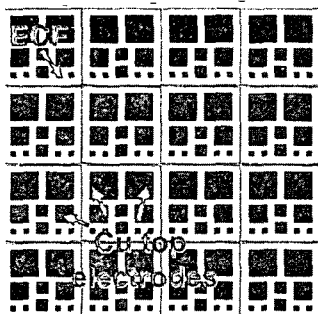
**4. ECF patterning by plasma etching**



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❖ Laminator



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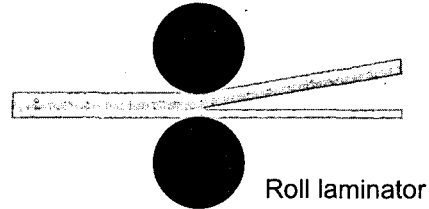
# ECF Lamination Process & Properties

➤ Pre roll lamination & Air lamination

✓ Pre roll lamination condition

- T = ~50°C
- Air lamination in vacuum

➤ ECFs properties in various size capacitor



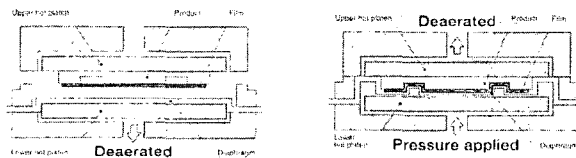
Capacitor size (mm)	4.5 x 4.5	3 x 3	2 x 2	1 x 1
Capacitance (pF)	528.4	238.4	107.9	29.0
Dielectric loss	0.0151	0.0154	0.0159	0.0175
Standard deviation of capacitance	11.32	5.41	2.77	1.05
Tolerance (3σ)	6.43	6.80	7.69	10.81

- ◆ Measurement condition
- Temp. = R.T.
- Frequency = 100kHz
- Sample size = (12x12cm<sup>2</sup>) x 2
- # of sample : (4.5x4.5, 3x3, 2x2 64 dot), (1x1 128 dot)

Tolerance much better than the ECF coated on a releasing film!

## Vacuum Laminated ECF

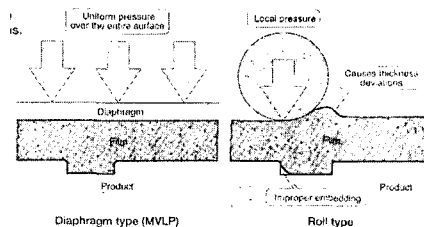
● Vacuum lamination method



▪ Vacuum lamination process

- ✓ Pre-lamination in 80°C (at SEMCO, vacuum method)
- ✓ Lamination in 180°C (at KAIST, conventional method)

● Comparison btw. Vacuum and roll lamination type



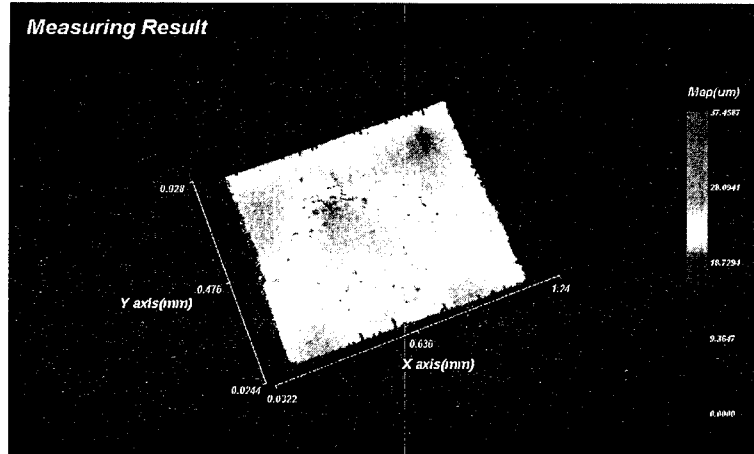
Properties	Capacitance tolerance (3σ)
Conventional laminated (coated on releasing films)	±8.39% (0.2025cm <sup>2</sup> ) ±11.55% (0.01cm <sup>2</sup> )
Conventional laminated (coated on Cu foil)	±7.76% (0.2025cm <sup>2</sup> ) ±10.03% (0.01cm <sup>2</sup> )
Vacuum laminated (coated on releasing films)	±3.57% (0.2025cm <sup>2</sup> ) ±9.49% (0.01cm <sup>2</sup> )
Vacuum laminated (coated on Cu foils)	±4.04% (0.2025cm <sup>2</sup> ) ±7.89% (0.01cm <sup>2</sup> )

▪ Capacitance tolerance

- ✓ Vacuum laminated type < Roll laminated type
- ✓ ECFs coated on Cu foils < coated on releasing films (# of samples : 92)

## Metal electrode area tolerance -White-Light Scanning Interferometer

- Measurement of electrode morphology
- ✓ Equipment : WSI (White-light Scanning Interferometer) in BUPE.
- ✓ CCD scale : 640x480 pixel, x5, resolution : few nm in z-axis
- ✓ Test sample must be reflective.

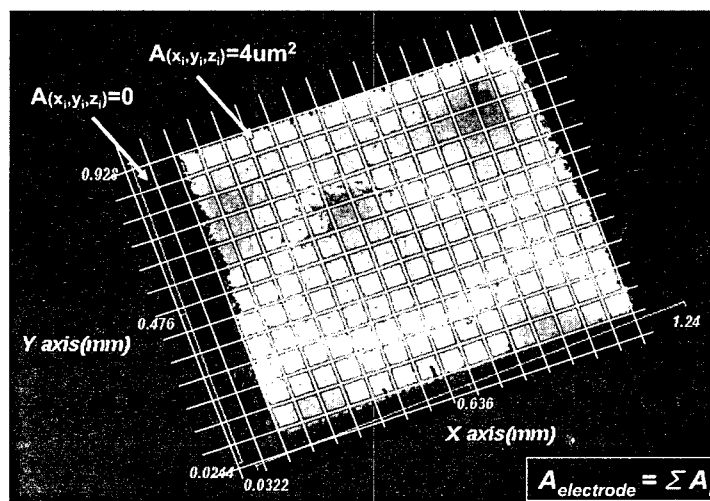


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## Calculation of Top Electrode Area

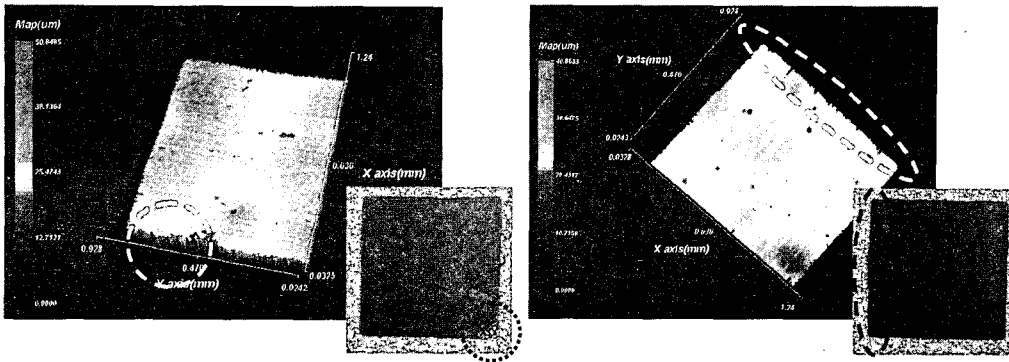
- RIE treated Cu had very low reflective index.
- Test samples were coated by 0.5um Cu using sputtering.
- Measured sample : 1x1mm<sup>2</sup> Cu electrode, # of samples : 92



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## Tolerance of Top Electrode Area



# of samples : 10 of 92

✓ Area tolerance of Cu electrode  $T_{\text{area}} = \pm 2.98\%$  ( $A_{\text{average}} : 1.0497\text{mm}^2$ )

✓ ECFs thickness tolerance  $T_{\text{thickness}} = \pm 1.74\%$

→  $T_{\text{total}} = T_{\text{area}} \times T_{\text{thickness}} = 6.33\%$  (Measured tolerance : 7.89%)

➢ Capacitance tolerance of ECFs was mainly determined by tolerance of electrode area, ECFs thickness, materials, and Cu surface roughness.

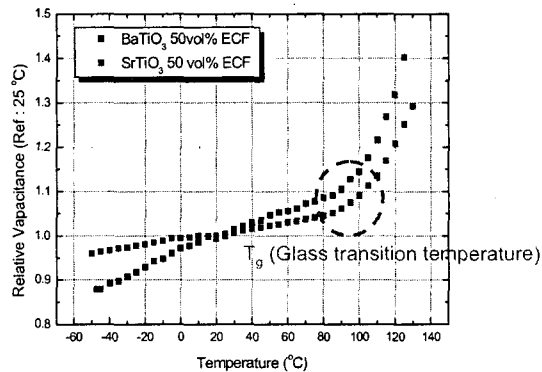
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## Temperature dependency of ECF capacitors

### ❖ Conventional ECFs

- Using thermo-electronic device, ECFs capacitor was heated and cooled.



➢ Requirements of cap. change for passive components (X7R, 'muRata co.'): 15% at -50°C ~ 125°C

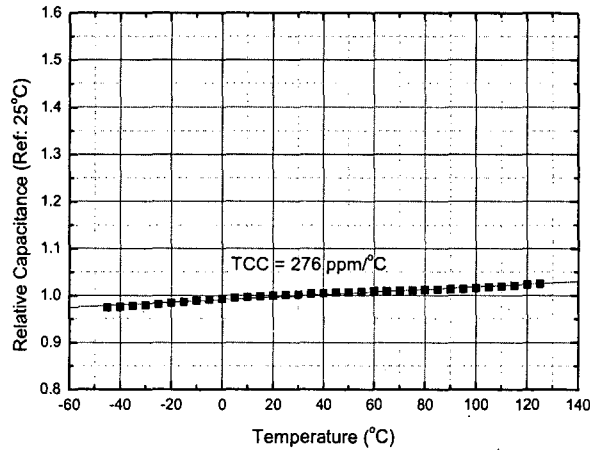
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# TCC of modified ECF capacitor

## ❖ Modified ECF capacitor

- Modified High Tg epoxy resin & SrTiO<sub>3</sub> powder were used
  - SrTiO<sub>3</sub> 50 vol% ECFs



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## Characterization of Materials for Gravure coating – TP & Solvents Contents

### ❖ Thermo-plastic resin contents

TP content (vol%)	40 (conventional)	45	50	60
Film forming capability	Only comma coating	Only comma coating	Only comma coating	Gravure available
Viscosity (Pas)	0.219	0.322	0.376	0.814

- ✓ BT powder contents : 50vol%
- ✓ New Solvents – less volatile solvent

### ❖ Solvent contents

Solvent content (cc)	12	14	16	18
Thickness (µm)	ECF not soluble	3.2	3.16	ECF not coated

- ✓ BT powder contents : 50vol%
- ✓ Thermo-plastic resin: 60vol%
- ✓ Gravure coating

(Solution 10cc 기준)

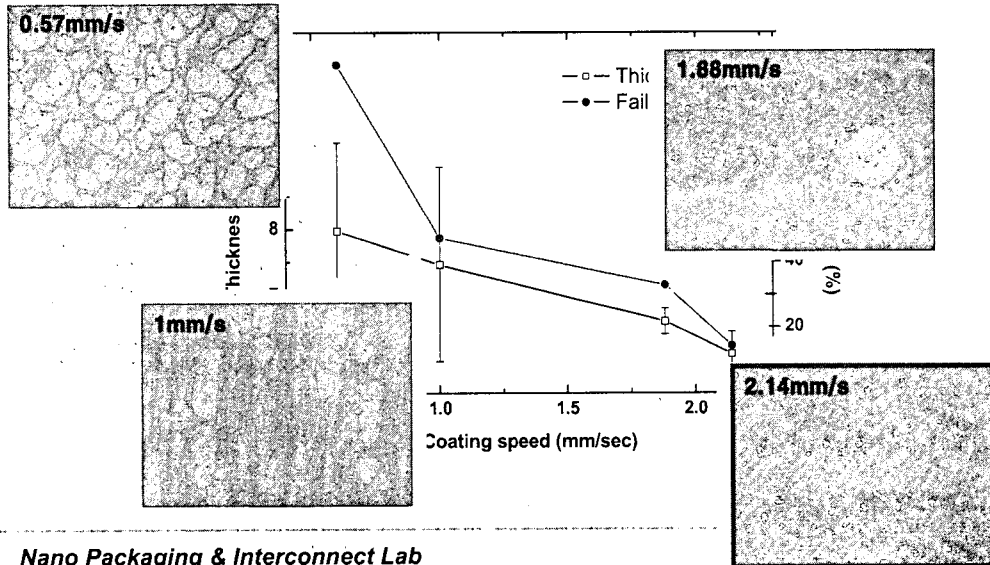
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# Characterization of Materials – Coating Speed

❖ Gravure coating speed

➤ Coating speed : 2.14mm/s



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## Characteristics of Comma & Gravure Coated ECFs ( on a PET releasing film)

❖ Failure reason of the Gravure coated ECF film

	Comma coated film	Gravure coated film (1 layer)	Gravure coated film (2 layer)
Dielectric loss	0.017	0.04	0.022
Thickness (μm)	12	3.16	6.09
Thickness tolerance (%)	1.74%	16.16%	4.38%
Capacitance (nF/cm <sup>2</sup> )	2.89	10.96	5.19 nF/cm <sup>2</sup>
Cap. Tolerance (%)	4.6	N/A	10.64
Failure	< 1%	61.5%	14.3%



✓ Capacitor electrode short problem  
 → Smoother surface PCB substrates needed.  
 → Pinholes and voids during coating and drying – resin

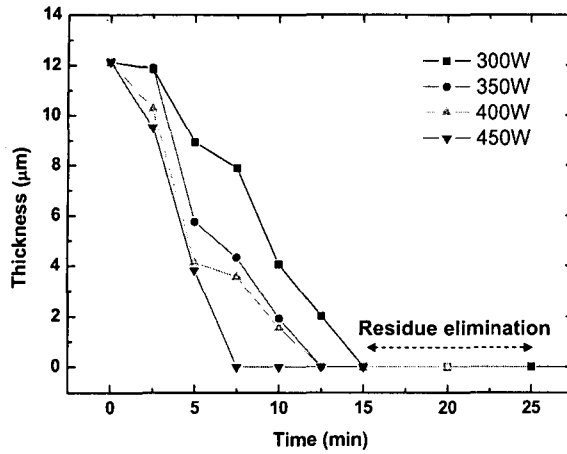
- Cap. Area = 4mm dia. (92 EA)
- Sputtered Cu top electrode
- BTO powder 50 vol.%

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## ECF Etching Process (RIE & Ultrasonic Cleaning)

• ECF thickness vs. RIE treatment time



➤ Gas: O<sub>2</sub>+CF<sub>4</sub>

➤ Ultrasonic cleaning

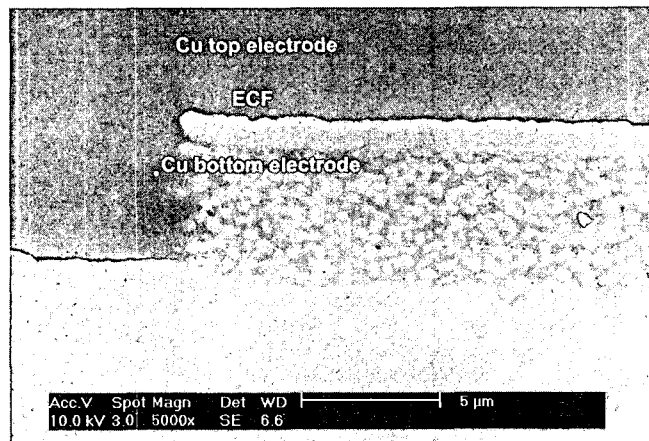
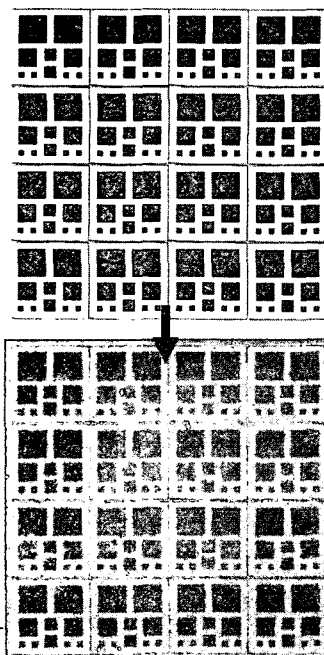


RF power (W)	300	350	400	450
Time (min)	35	25	20	15

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## Patterned ECFs by Plasma Etching



Cross-sectional image of a plasma etched embedded capacitor  
With 7 µm ECF and 1µm sputter-deposited Cu

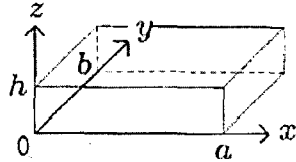
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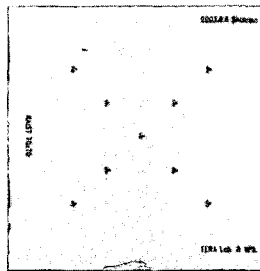
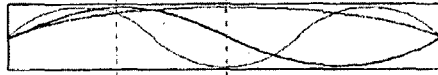


## $\epsilon_r$ – high frequency measurement

### ◆ Rectangular cavity resonator



### ▪ Distribution of electric field in cavity resonator



### ❖ Resonance frequency

$$f_{mn} = \frac{c}{\sqrt{\epsilon_r}} \sqrt{\left(\frac{m}{2a}\right)^2 + \left(\frac{n}{2b}\right)^2}$$

- m, n: cavity mode numbers
- c: speed of light
- $\epsilon_r$ : relative permittivity

### ❖ Test conditions

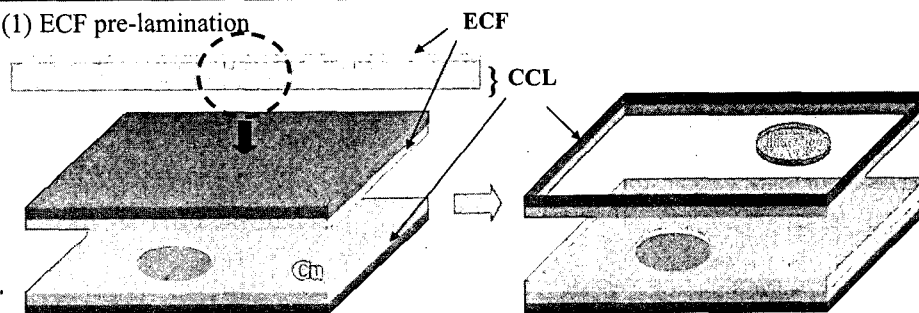
- Equipment : HP8510C
- Frequency range : 100MHz ~ 15GHz
- Frequency step size : 25MHz
- S11 parameter (reflection parameter)
- Sample size : 60mm×60mm

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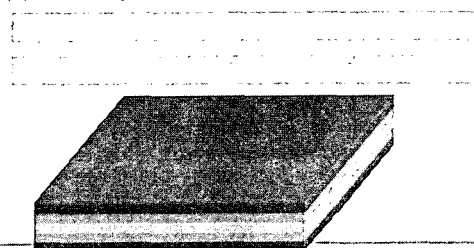
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## ECF Embedding in PCB & Electrodes Formation

### (1) ECF pre-lamination



### (2) Bonding & Lamination



◆ ECFs had tacky and little viscosity in B-stage. → By only PCB etching process, electrode formation is available and there was no void between electrode and PCB.

### ◆ Pre-lamination condition

80°C (B-stage), 3.54kgf/cm<sup>2</sup>

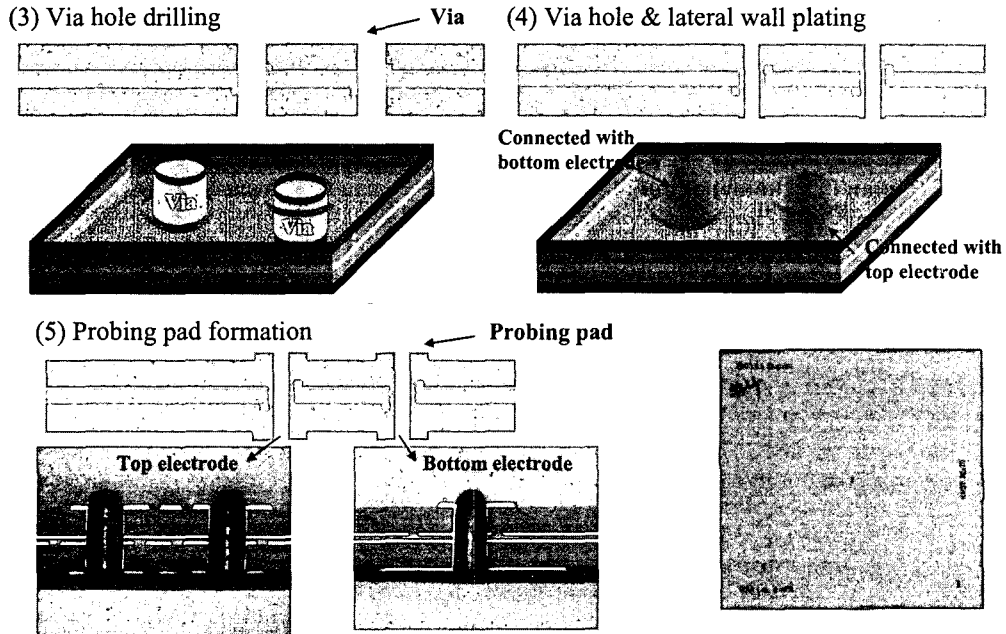
### ◆ Lamination condition

180°C, 3.54kgf/cm<sup>2</sup>, 10min

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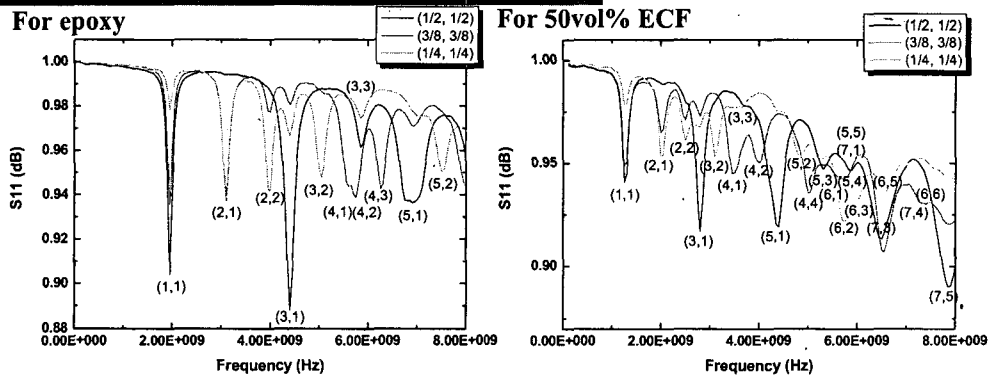
# ECF Embedding in PCB & Electrodes Formation



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## Result – Epoxy & Powder A 50vol% ECF



◆ Mode numbers were identified for each resonance frequency

◆ Rules

- ✓ (1/2, 1/2) point → 2× mode impossible
- ✓ (1/4, 1/4) point → 4× mode impossible
- ✓ (3/8, 3/8) point → 8× mode impossible

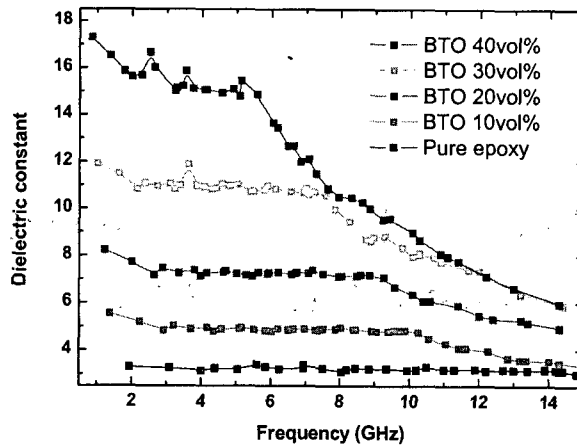
◆ As dielectric constant is bigger, the resonance frequencies were shown at lower frequency.

$$f_{mn} = \frac{c}{\sqrt{\epsilon_r}} \sqrt{\left(\frac{m}{2a}\right)^2 + \left(\frac{n}{2b}\right)^2}$$

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## $\epsilon_r$ – high frequency measurement



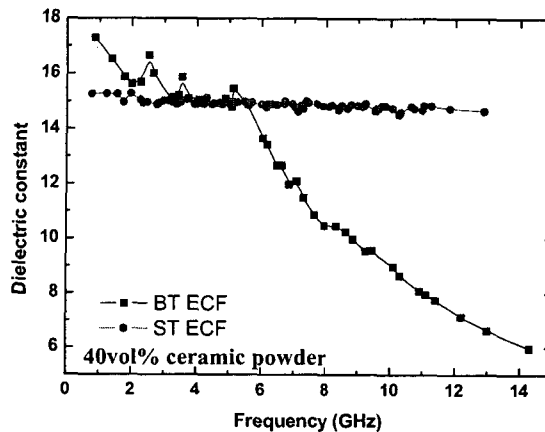
- As powder loading increases,
  - Dielectric relaxation reveals at lower frequency.
  - ➔ Effect  $\text{BaTiO}_3$  particles is bigger than that of epoxy matrix.

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## Frequency Dependency of Dielectric Constants

- ◆ Measurement condition
  - Rectangular cavity resonator method
  - Frequency range : 100MHz ~ 15GHz
  - Equipment : HP8510C Network analyzer



- BT ECF showed dielectric relaxation at ~5GHz, but ST ECF showed no relaxation.

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## Epoxy/BaTiO<sub>3</sub> Composite Embedded Capacitor Pastes (ECPs)

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### *Advantages & Disadvantages of ECPs*

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#### *Advantages*

Capacitors can be formed in **local area** via a screen printing method.  
Simple process for embedded capacitors fabrication.  
Higher powder volume loading. (compared with ECF coating process)



#### *Disadvantages*

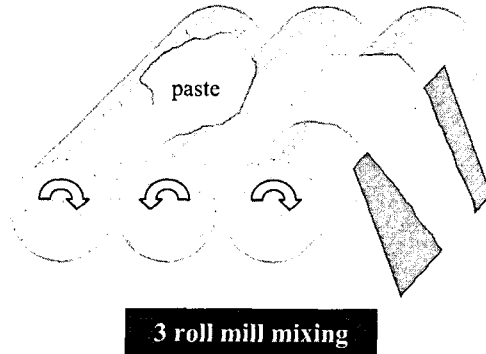
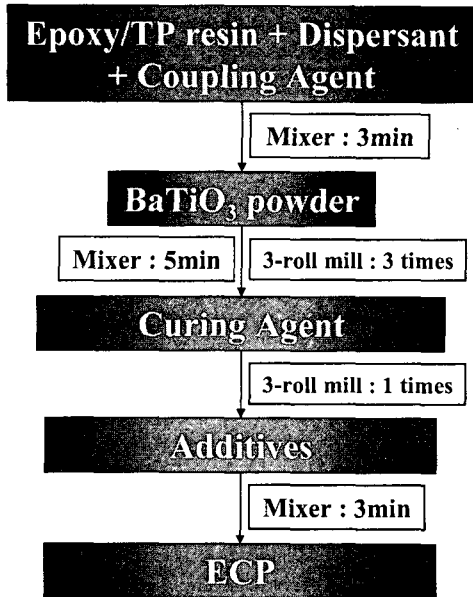
Less tolerances (surface morphology and thickness)  
Lower Repeatability (Sometimes unstable to hold their values over time and temperature)

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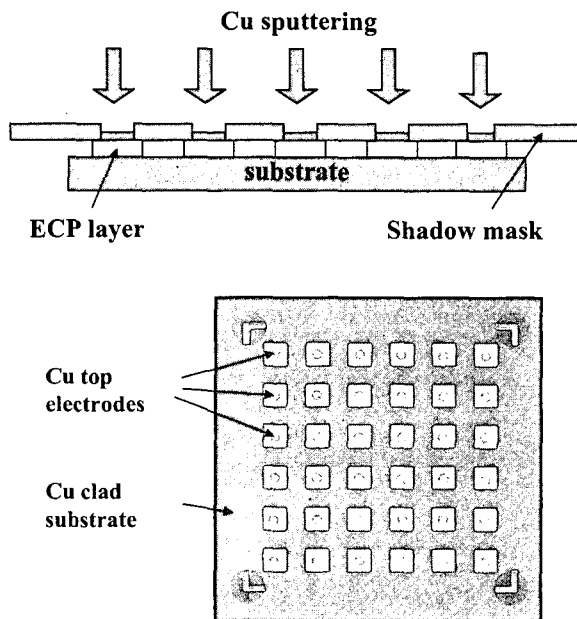
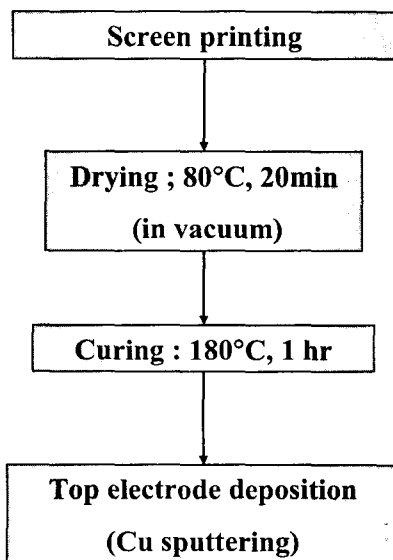
## Procedure of fabricating ECPs



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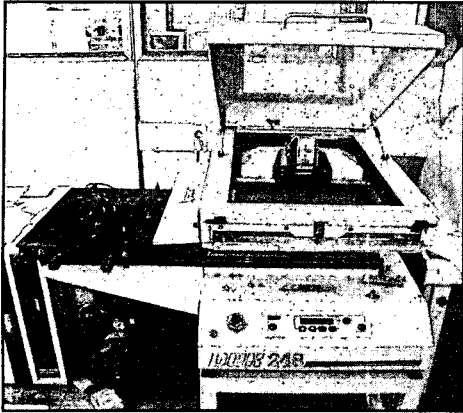
## Capacitor fabrication procedure



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Sample Image

## Optimization of screen printing parameters



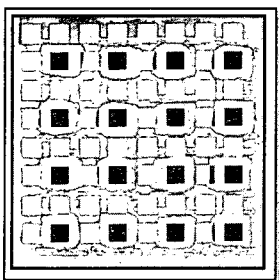
DEK 248 Screen Printer

- Squeegee hardness : 90 durometer
- Squeegee angel : 45°
- Printing mask mesh : 325 mesh
- Mask emulsion thickness : 10  $\mu\text{m}$
- Snap-off distance : 1mm
- Printing speed : 30mm/s

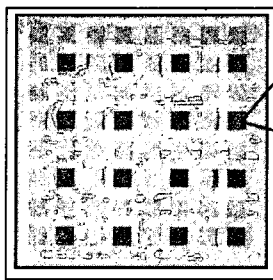
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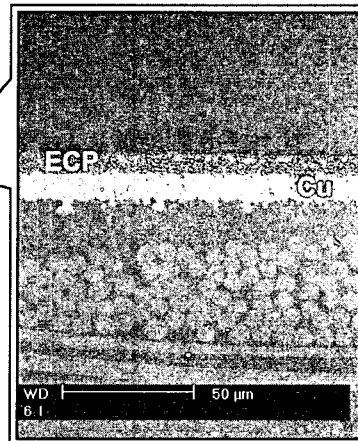
## Thickness enhanced & plasma etched ECP capacitor



Top electrode patterned  
(lithography)



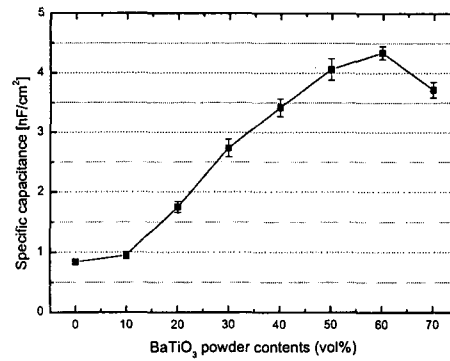
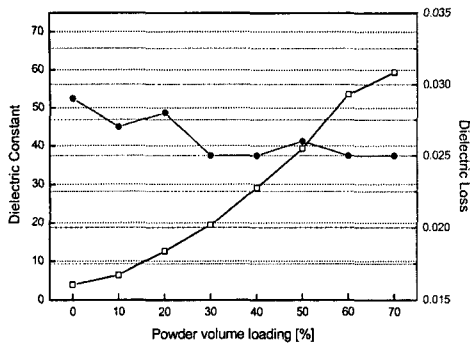
After RIE



- Powder content : 50vol%
- Specific capacitance : 2.6 nF/cm<sup>2</sup>
- Dielectric Thickness : ~ 11 $\mu\text{m}$
- Capacitance Tolerance ( $=3\sigma$ ) : 22.6 %
- Average dielectric loss : 0.023

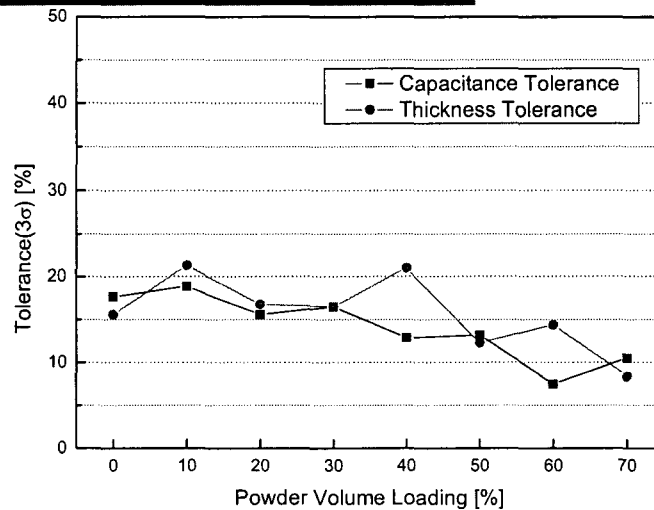
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## $\epsilon_r$ and specific capacitance at 100kHz



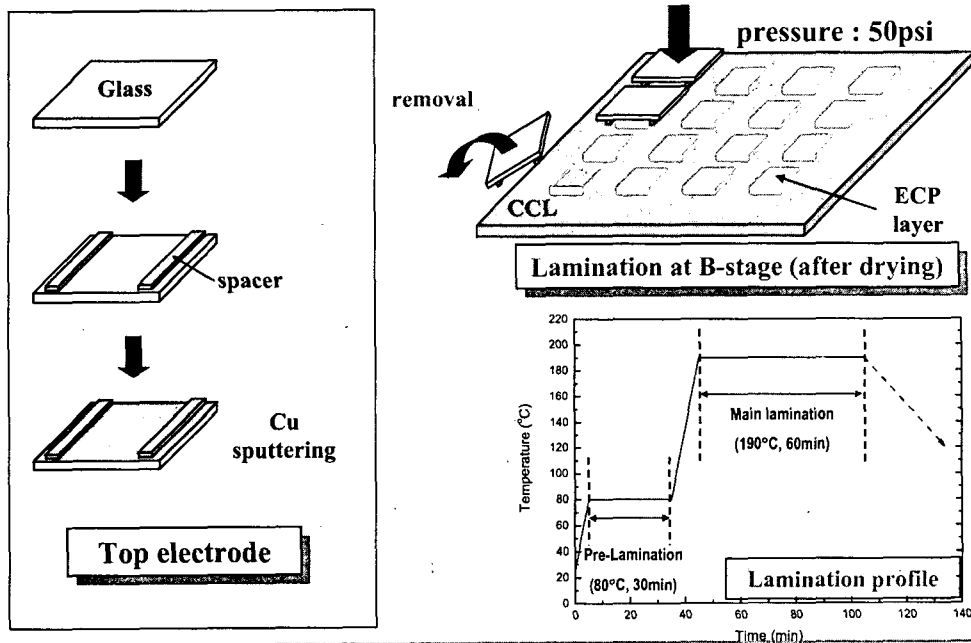
- Maximum dielectric constant was about 60 at 70vol%.
- But maximum specific capacitance, 4.34 was obtained at 60vol%.
- Tolerance has lower value at higher volume loading.

## Tolerance



- Tolerance has lower value at higher volume loading.

## Modified lamination method (patent pending)



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## Summary & Conclusions

- ◆ PCB substrate compatible less than 10% low tolerance BaTiO<sub>3</sub> ECFs were successfully demonstrated on 14 X 14 cm PCB substrates.
- ◆ ECFs can be selectively etched using a plasma etching.
- ◆ Dielectric constants of epoxy/BaTiO<sub>3</sub> ECF in 0.1~10GHz range were measured using a cavity-mode resonator method.
  - Dielectric relaxation of ECFs was caused by transferred from dipole polarization region to ion polarization region.
  - As powder loading increased, relaxation frequency decreased.
- ◆ At high frequency range, SrTiO<sub>3</sub> ECFs show more stable dielectric behavior than BaTiO<sub>3</sub> ECFs.
- ◆ Less than 10 micron thickness and low tolerance ECPs were successfully demonstrated using a screen printing and planarization technique.

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